

**WHAT IS CLAIMED IS:**

1        1. A method of using an interferometric confocal microscope to measure features of  
2 a trench or via in a substrate, wherein the interferometric confocal microscope produces a  
3 measurement beam, the method comprising:

4                focusing the measurement beam at a selected location at or near the bottom of the  
5 trench or via to excite one or more guided-wave modes within the trench or via;

6                measuring properties of a return measurement beam that is produced when the  
7 measurement beam is focused at the selected location, said return measurement beam  
8 including a component corresponding to a radiated field from the one or more guided-wave  
9 modes that are excited within the trench; and

10                determining the features of the trench or via from the measured properties of the  
11 return measurement beam.

1        2. The method of claim 1, further comprising scanning the measurement beam in a  
2 direction that is substantially normal to the substrate to locate the bottom of the trench or via.

1        3. The method of claim 1, wherein determining features involves determining a depth  
2 of the trench or via.

1        4. The method of claim 1, further comprising:

2                focusing the measurement beam at a selected distance above the surface of the  
3 substrate and over the trench or via; and

4                measuring properties of a return measurement beam that is produced when the  
5 measurement beam is focused at the selected distance above the surface of the substrate and  
6 over the trench or via,

7                wherein determining the features of the trench or via involves combining  
8 measurements of properties of the first-mentioned return measurement beam and  
9 measurements of properties of the second-mentioned return measurement beam.

1       5. The method of claim 4, wherein the selected location is a distance Z1 below the  
2 top surface of the substrate, where the selected distance is a distance Z2 above the surface of  
3 the substrate, and wherein Z1 equals Z2.

1       6. The method of claim 1, wherein the one or more guided-wave modes that are  
2 excited are leaky guided-wave modes.

1       7. The method of claim 1, further comprising generating a measurement beam that is  
2 asymmetric.

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4       8. The method of claim 1, further comprising generating a measurement beam that is  
5 asymmetric.

1       9. The method of claim 1, wherein measuring the properties of the return  
2 measurement beam comprises measuring conjugated quadratures of fields of the return  
3 measurement beam.

1       10. The method of claim 4, wherein measuring properties of the field of a return  
2 measurement beam that is produced when the measurement beam is focused at the selected  
3 distance above the surface of the substrate and over the trench or via comprises measuring  
4 conjugated quadratures of fields of that return measurement beam.

1       11. The method of claim 10, wherein determining the features of the trench or via  
2 involves combining the measurements of conjugated quadratures of fields of the return  
3 measurement beam that is produced when the measurement beam is focused at the selected  
4 location and measurements of conjugated quadratures of fields of the return measurement  
5 beam that is produced when the measurement beam is focused at the selected distance above  
6 the surface of the substrate and over the trench or via.

1       12. The method of claim 1, wherein measuring the properties of the return  
2 measurement beam involves using a bi-homodyne detection technique.

1           13. The method of claim 1, wherein measuring the properties of the return  
2    measurement beam involves using a quad-homodyne detection technique.

1           14. The method of claim 1, wherein the interferometric confocal microscope is a far-  
2    field interferometric confocal microscope and the measurement beam is a far-field  
3    measurement beam.

1           15. The method of claim 1, wherein the interferometric confocal microscope is a  
2    near-field interferometric confocal microscope and the measurement beam is a near-field  
3    measurement beam.

1           16. The method of claim 1, further comprising performing the steps of focusing  
2    and measuring at a plurality of locations along the bottom of the trench to detect a  
3    defect within the trench, wherein said selected location is one of said plurality of  
4    locations.

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